

In the Claims

Claims 1-65 (cancelled).

Claim 66 (original): A method of forming aligned structures with a radiation-sensitive material, comprising, in the following sequential order:

providing a substrate having a radiation-sensitive material thereover; the substrate and radiation-sensitive material having at least three defined regions; the at least three defined regions including a first region, a second region and a third region;

exposing the first region of the radiation-sensitive material to a first dose of actinic radiation; exposing second region of the radiation-sensitive material to a second dose of actinic radiation less than the first dose; and leaving the third region of the radiation-sensitive material not exposed to either the first or second dose of the actinic radiation;

developing the radiation-sensitive material; the developing removing the radiation-sensitive material from over the first region of the substrate, and leaving the radiation sensitive material over the second and third regions of the substrate;

treating the first region of the substrate;

exposing the second and third regions of the radiation-sensitive material to a blanket dose of the actinic radiation;

developing the radiation-sensitive material; the developing removing the radiation-sensitive material from over the second region of the substrate, and leaving the radiation sensitive material over the third region of the substrate; and

while the radiation-sensitive material remains over the third region of the substrate, treating the second region of the substrate.

Claim 67 (original): The method of claim 66 wherein the substrate corresponds to a radiation-patterning tool substrate and comprises a layer of opaque material over a transparent base; the treating of the first and second regions comprising removing the opaque material from over the base.

Claim 68 (original): The method of claim 67 wherein the treating of the first region further comprises etching into the base.

Claim 69 (original): The method of claim 67 wherein the treated first region corresponds to a rim shifter or outrigger; wherein the treated second region corresponds to a feature; and wherein the rim shifter or outrigger modifies a pattern produced by the feature during a printing operation utilizing the radiation patterning tool substrate.

Claim 70 (original): The method of claim 67 wherein the treated second region corresponds to a rim shifter or outrigger; wherein the treated first region corresponds to a feature; and wherein the rim shifter or outrigger modifies a pattern produced by the feature during a printing operation utilizing the radiation patterning tool substrate.

Claim 71 (original): The method of claim 66 further comprising removing the radiation-sensitive material from over the third region, and subsequently utilizing the substrate as a radiation-patterning tool during a printing operation.